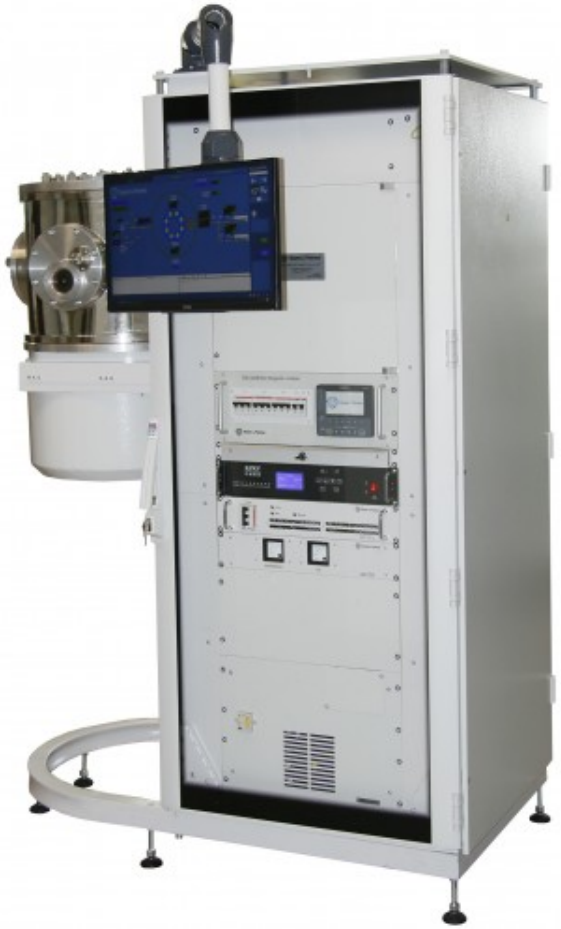
Beams & Plasmas
Laboratory of vacuum technologies plus, LLC

# Ion etching unit NIKA-155



Ion cleaning unit Nika-2012 IO GDO is designed for removal of residues of contamination of finishing pastes that are not washed away by washing
liquids, from the pores of wear-resistant coatings of parts of gas-dynamic supports
(GDO) (products) with an argon ion beam.

The vacuum chamber of the installation is equipped with the following technological
devices:

- ion source IBS-125
- carousel with vertical rotation of satellites (8 pcs.) for the installation of product carriers;
- temperature sensor (DT);
- two viewing windows.

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## Layout and characteristics

**IBS-125** - Ion Beam Source

**Temperature sensor**

**carousel with vertical rotation of satellites (8 pcs.) for unit**

| **Parameters** | |
|---|---|
| Power | 9 kW |
| Supply voltage | 380V + 10-15% |
| Time to reach the working vacuum | No more than 30 minutes |
| Number of gas injection channels | 2 |
| Maximum current consumption per phase | 14 A |
| Weight | no more than 500 kg |
| Coolant volume | No more than 15 l |
| Coolant | distilled water, 20% ethyl alcohol solution in distilled water |
| Ultimate vacuum | no more than 1 × 10-3 Pa |
| Working gases | argon |
| Working vacuum | 4 × 10-3 Pa |

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